000111110001

Cascade TESLA200

200 mm On-Wafer Power Semiconductor Probing System

Overview

Designed specifically for IGBT/power MOSFET (GaN, SiC, Si) device measurements at the wafer level, the new TESLA200 on-wafer power semiconductor probing system is engineered to provide accurate data up to 3,000 V (triaxial) / 10,000 V (coaxial) and 200 A (standard) / 600 A (high current). With next-generation test capabilities, anti-arcing solutions, wafer automation, and support for both engineering probes and T.I.P.S. "LuPo" High Voltage / High Power Probe Cards, the TESLA200 now enables complete thermal testing (-55°C to 300°C) with fully-automatic thin / TAIKO wafer loading. One system covers all on-wafer high power test needs, from R&D to niche production.

The new TESLA200, available in semi-automatic and fully-automatic models, is scalable and field upgradeable, allowing it to meet any budget requirements. The system is ideal for collecting high accuracy measurement data on single or volume wafers as fast as possible, and can be utilized in R&D, device characterization/modelling or niche production applications.



Patented AttoGuard® and MicroChamber® technologies built in TESLA200 significantly improve low-leakage and low-capacitance measurements. In combination with FormFactor's patented TESLA FemtoGuard™ thermal chuck technology, the TESLA200 provides an ultra-low noise, fully guarded and shielded test environment. The high-power TESLA FemtoGuard chuck also incorporates MicroVac™ technology enabling low-contact resistance, thin-wafer handling and maximum power dissipation.

To ensure the utmost safety during high-voltage measurements, the TESLA200 on-wafer power semiconductor probing system employs a TUV-certified safety interlock system integrated with an ergonomic clear enclosure. With an advanced 200 mm fast stage, automatic wafer loader and thin wafer handling capability, TESLA200 provides everything needed for scientists, R&D / test engineers, or production operators to get their job done fast.



> Features / Benefits

High-voltage / Current Probes	 On-wafer power device characterization up to 10,000 V DC / 600 A
	 Reduced probe and device destruction at high currents up to 20 A DC and 300 A pulse (600 A when two probes are used in parallel)
	 Increased isolation resistance and dielectric strength to provide full triaxial capability at high voltage (3,000 V) for low-leakage measurement
T.I.P.S. "LuPo" High Voltage /	On-wafer power device characterization up to 10,000 V DC
High Power Probe Cards	 Safe and convenient integration kits to support T.I.P.S. "LuPo" High Voltage / High Power Probe Cards
Gold-plated TESLA High-power	Prevent thin wafers from curling and breaking
MicroVac Chucks	Advanced MicroVac chuck surface for minimum contact resistance between wafer and chuck
	Accurate Rds(on) measurement at high current
	Accurate UIS measurements at high temperature
Safety for Operator	Safety interlock system with clear enclosure for operator safety during device measurements
	Roll-out stage for full wafer access and easy wafer loading/unloading
Seamless Integration	 Convenient connection kits for easy and safe system integration with power device analyzers from Keysight Technologies and other major suppliers
	 Seamless integration between Velox and analyzers/measurement software
Productivity	High throughput wafer auto-loading (standard, thinned, warped, TAIKO)
	 Contact Intelligence enables higher yield, accurate Rds vertical device measurements over temperature automatically
	• Easy on-screen navigation, wafer mapping, and operation of accessories with Velox software

> Available Models



Semi-automated Probe System



Fully-automated Probe System



> Power Handling

Tesla Chucks	Coax	Standard**	High Current**
Max voltage*	10 kV (coaxial)	3,000 V (triaxial), 10 kV (coaxial)	3,000 V (triaxial), 10 kV (coaxial)
Max current	200 A (pulsed), 10 A (DC)	200 A (pulsed), 10 A (DC)	600 A (pulsed), 20 A (DC)
Power dissipation			100 W generated in 1 cm2 area at -40°C

^{*} Limited to 3kV for lift pin chucks. For automatic handling at higher test voltages, use non-liftpin chuck in combination with top-side wafer end effector.

Measurement Performance

Typical Chuck Noise (Triaxial)**

		TESLA20	0 AP Models	TESLA20	0 M Models	Settling Time***
		Standard	High Current	Standard	High Current	
10 V	-55°C/-50°C/-40°C	20 fA	180 fA	40 fA	180 fA	< 200 fA @ 1.0 sec
	25°C	20 fA	40 fA	40 fA	40 fA	< 200 fA @ 0.5 sec
	200°C	25 fA	120 fA	40 fA	120 fA	< 200 fA @ 1.0 sec
	300°C	30 fA	240 fA	60 fA	240 fA	< 200 fA @ 2.0 sec
3 kV	-55°C/-50°C/-40°C	2 pA	4 pA	4 pA	4 pA	< 15 pA @ 1.5 sec
	25°C	2 pA	4 pA	4 pA	4 pA	< 15 pA @ 1.5 sec
	200°C	3 рА	4 pA	6 pA	4 pA	< 15 pA @ 1.5 sec
	300°C	6 pA	12 pA	10 pA	12 pA	<15 pA @ 4.5 sec

Typical Chuck Leakage (Coaxial)

		TESLA200	AP Models	TESLA200	M Models	
		Coax / Standard	High Current	Coax / Standard	High Current	
3 kV	-55°C/-50°C/-40°C	2 nA	4 nA	2 nA	4 nA	
	25°C	2 nA	4 nA	2 nA	4 nA	
	200°C	2 nA	4 nA	2 nA	4 nA	
	300°C	4 nA	10 nA	4 nA	10 nA	
10 kV	-55°C/-50°C/-40°C	7 nA	10 nA	7 nA	10 nA	
	25°C	7 nA	10 nA	7 nA	10 nA	
	200°C	7 nA	12 nA	7 nA	12 nA	
	300°C	14 nA	34 nA	14 nA	34 nA	

System Residual Capacitance

	TESLA200 AP Models	TESLA200 M Models	
Capacitance	4.0 pF	40 pF	

^{**} Overall leakage current is comprised of two separate components: 1) offset, and 2) noise. Offset is the DC value of current due to instrument voltage offset driving through isolation resistance and instrument offset current itself. Noise is low-frequency ripple superimposed on top of offset and is due to disturbances in the probe station environment. Noise and leakage are measured with a B1505A- B1510A (HPSMU) and or B1513A/B/C with Cascade Microtech setups or equivalent; is sample interval, auto or 1 nA range, 1 µA compliance, 40 PLC integration. Typical noise values are defined using the standard deviation. The maximum peak noise value may be 2-3 times higher than typical noise values depending on environmental factors such as humidity, vibration, temperature fluctuation, condition of the cable and connectors etc.



^{**} Performance is determined/selected with the connection breakout cable connecting the universal chuck connector to the instrument. Either max. voltage or max. current can be achieved, not simultaneously.

^{***} Settling time is measured with a B1505A/HPSMU Cascade Microtech setup or equivalent; 2 ms sampling interval, Fixed range: 1 nA, 1 µA compliance, 1 NPLC integration.

> High Power Probes for TESLA200

Probe UHP HCP-XX HVP-XX Current Up to 300 A Up to 100 A Up to 5 A

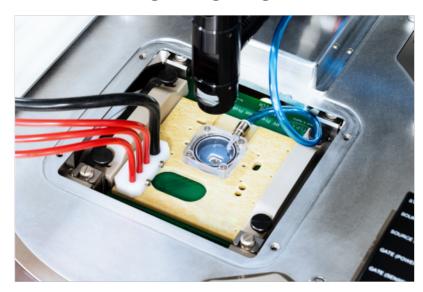
Up to 500 V

Up to 3,000 V

Up to 10,000 V

Voltage

> T.I.P.S. "LuPo" High Voltage / High Power Probe Cards



- Chip scale pressure chamber surrounds DUT to increase breakdown voltage
- \bullet On-wafer power device characterization up to 10,000 V DC
- \bullet Non-thermal and thermal probe cards with temperatures up to 200°C
- Engineering and production probe cards



TESLA200

^{*}See High-Power Probe data sheet for more information.

> MicroChamber Performance

Electrical	TESLA200 AP Models	TESLA200 M Models	
Integrated technologies	AttoGuard and PureLine		
EMI shielding	≥ 20 dB 0.5-3 GHz	≥ 20 dB 0.5-20 GHz (typical)	
	≥ 30 dB 3-20 GHz (typical)		

Light Shielding

Туре	Complete dark enclosure around chuck	
Wafer access	Front access door with rollout stage for easy manual wafer loading	
	Side access door for fully automatic wafer loading	
Probe compatibility	Standard MicroChamber TopHat™ allows access for up 8 probes	
	Quad MicroChamber TopHat™ allows access for up 4 probes	
Light attenuation	≥ 120 dB	

Purge and Condensation Control

Test environment	Low volume for fast purge, external positioning and cable access to maintain sealed environment	
Dew point capability	>-65° C for frost-free measurements*	
Purge gas	Dry air or nitrogen*	
Purge flow rate	Standard purge - manual controls, variable 0 to 110 l/min (4 CFM) at SATP	
	Quick purge - manual/automated software control, standard purge rate or maximum > 110 l/min (4 CFM) at SATP*	
Purge time	15 min for measurements @ -55°C (typical)	
External condensation control	Integrated laminar-flow air distribution on external MicroChamber surfaces to eliminate condensation	
	Controls for ON/OFF and flow rate for both top and bottom surfaces	

^{*}See Facility Planning Guide for details.



➤ Mechanical Performance*

X-Y Stage	Semi-/Fully-automated	
Travel	203 mm x 203 mm (8 in. x 8 in.)	202 mm x 203 mm (3 in. x 8 in.)
Motion control	High performance stepper motors and manual remote control	Manual controls (84-Y direct rotary knobs)
Resolution	0.2 μm (0.008 mils)	5 nm / turn
Feedback system	Closed loop optical linear encoder	
Max speed	Up to 100 mm/sec (4 in./sec)	

X-Y Speed/Accuracy	Fast Mode	Standard Mode	Accurate Mode
Accuracy	≤5.0 μm	≤2.5 µm	≤2.0 μm
Repeatability	≤3.5 μm	≤2.0 µm	≤1.5 µm
Typical stepping time for a 200Z – 1000X/Y – 200Z μm movement	550 ms	750 ms	960 ms

Note: Shown values are typical values and can slightly vary depending on machine configuration.

Z Stage	Semi-/Fully-automated	Manual
Travel	35 mm (1.4 in.)	Fixed Z mount
Resolution	1 μm (0.04 mils)	
Repeatability	≤1 µm (0.04 mils)	

Theta Stage	Semi-/Fully-automated		
Travel	± 7.5°	±5.7°	
Resolution	0.5 μm (0.02 mils)**	0.2° / turn	
Repeatability	<1.5 μm (0.06 mils)**		
Accuracy	± 2 μm (0.08 mils)** standard moves ± 3 μm (0.12 mils)** large moves		

^{*} Specification valid for standard chuck. Mechanical performance might slightly deviate for high current chuck.



^{**}Measured at edge of 200 mm chuck

> Platen System

Platen

Material	Steel for magnetic positioners	
Dimensions	74.5 cm (W) x 63.5 cm (D) x 20 mm (T) (29.3 in. x 23.4 in. x 0.78 in.)	
Mounting system	Kinematic or fixed	
Accessory compatibility	Minimum of 8 DC or 4 RF positioners allowed, compatible simultaneous probe card holder use	
HTS thermal management	Integrated laminar-flow air-cooling for thermal expansion control	
Standard interface	For MicroChamber, TopHat, probe card holders and custom adapters	
Platen Lift*		
Туре	Precision 4-point linear lift	
Range**	5.0 mm (0.20 in.)	
Repeatability	≤ 3 µm (0.12 mils)	
Lift control	Ergonomic handle with 90° stroke. Optional micrometer control for fine adjustment of probe card contact.	

^{*} Optional on some models.

> Platform

General

Physical dimensions	Please consult Facilities Planning Guide	
Vibration isolation	olation Attenuation ≥ 0 dB @ 6 Hz, 5 dB per octave @ 6 Hz to 48 Hz,≥ 15 dB above 48 Hz*	
Probe-force capability	20 kg (44 lb.) maximum	
Probe-force deflection	≤ 0.0015 µm/µm slope per 10 kg load	
System chuck planarity** (thermal chuck)	< 20 μm (0.8 mils) @ 25°C	
	< 30 μm (1.2 mils) @ -60°C	
	< 30 μm (1.2 mils) @ 200°C	
	< 40 μm (1.6 mils) @ 300°C	
Station Controller	High-performance system controller with Velox probe station control software and Windows 10	
Die cycling	Chuck stepping time ≤ 0.75 sec (200 μm Z down − 1000 μm X-Y − 200 μm Z up)	

^{*} Please see facilities planning guide for minimal environment background vibrations.

Communication Ports

Туре	User-accessible	Location	Note
USB 2.0	0	Station Controller - Rear	For security keys and USB instrument control
USB 2.0	(2)	Station Controller - Front	
USB 3.0	1	Station Controller - Rear	
LAN GbE	1	Station Controller - Rear	
RS-232	2	Station Controller - Rear	For instrument control (thermal, microscope, etc).
GPIB IEEE 488.2	1 (option)	Station Controller - Rear	Supplied with USB adapter for test instrument control

Accessory Interface Ports

Туре	Qty	Location	Note
Edge-sense	1	IO- / Pneumatic module	Probe card contact sense
INKER	2	IO- / Pneumatic module	Control for die inker



^{** 3.0} mm for application layers that exceed the platen size to the left

^{**} Calibrated within 180 mm diamater area at 25° C.

> Wafer and AUX Chuck

Vacuum actuation

/ Water and AUX Chuck			
Wafer Chuck	Coax	Standard	High Current
Туре	HV Coaxial (standard & 3kV)	HV FemtoGuard Triaxial	HV FemtoGuard Triaxial
Diameter			
200 mm (8in.) - Thermal	•	•	•
200 mm (8in.) - Non Thermal	•	•	
Material	Gold (Au) plated aluminum		
Electrical connection	Dual HV triax cables with integr	ated chuck port (except Coax 3kV	- SHV connectors)
Supported measurement modes			
Coaxial	•	•	•
Triaxial	•	•	
Vacuum uniformity	Patented MicroVac technology using 495 micro-hole pattern for uniform vacuum hold down of thin, warped and partial wafers, and uniform temperature conductivity.		
Vacuum zones	5 selectable zones, with hole patterns arranged in approximately 9, 70, 93, 143 and 178 mm diameters (0.4, 2.8, 3.8, 5.6 and 7 in.)		
Vacuum actuation	Easy access multi-zone manual vacuum controls, and software control (semi-automated)		
Thin wafer support	Thin wafers down to 50 μm and optional support for Taiko wafers		
Auxiliary Chucks			
Quantity	Up to three total AUX chucks		
Design	High-voltage 10 kV compatible		
Substrate size (maximum)	15.2 mm x 22.1 mm (0.59 in. x 0.87 in.) ISS substrate		
	19 mm x 19 mm (0.75 in. x 0.75 ir	n.) substrate	
Material	Absorber (magnetically loaded)		
	Ceramic		
Thermal isolation	Ensures negligible load drift on ISS		
Flatness	≤8 µm (0.3 mils) adjustable plar	narity	

Independently controlled apart from wafer vacuum zones



TESLA200

> Tesla Safety Systems

TUV-certified Safety System and Enclosure for TESLA200 Power Semiconductor Probing System

- Safety-rated interlock system for high-power testing (meets EN 60947-5-1, EN 60204-1)
- Impact resistant safety approved clear enclosure
- Front opening door for ergonomic test setup and operation
- Side and rear access panels for easy equipment configuration
- Integrated design using TESLA200 universal mounting system



TESLA200 Semi-automated Model



TESLA200 Fully-automated Model

> Wafer Loader

Test Automation

Supported cassettes	25 wafers with 100 mm or 150 mm (SEMI E1) or 200 mm (SEMI E1 like)*	
Cassette stations	Up to 2	
Wafer handling	Wafers in compliance with SEMI M1	
	Handling of non-SEMI M1 compliant ("thin") wafers to be tested prior to quote, special solutions available	
Pre-alignment	Optical pre-aligner with flat/notch detection	
	Translucent wafer materials require test prior to quote	
Wafer ID reading	Optional at top or bottom side (user changeable)	
	Supports barcode (BC 412 SEMI T1-95 standard) and IBM 412, OCR text (SEMI M12, M13 and M1.15 standard),	
	IBM, triple and OCR-A fonts or 2D code (Data Matrix T7 and M1.15 standard)	
Quick access port	Optional — storage of up to 2 wafers (100 mm / 150 mm / 200 mm) for throughput enhancement or procedure support	
Wafer handling @ ambient	≤ 18 sec cassette load (incl. wafer scan) after latching door	
	≤ 38 sec first wafer (cassette → pre-aligner → prober chuck) (SEMI M1 wafer)	
	≤ 47 sec next wafer with quick access port (prober chuck → wafer unload and next wafer → prober chuck)	
	≤ 57 sec next wafer without quick access port (prober chuck → wafer unload and next wafer → prober chuck)	
Automation management	Integrated into Velox Probe Station Control Software.	
	The creation of workflows and receipts is as simple as it can get.	

9



^{*} Restrictions may apply for 200 mm cassettes of some vendors, as there is no uniform standard. Double-check required to confirm compatibility.

> Wafer Loader (continued)

Wafer End Effector

X2-EHS48	Wafer end effector for auto-loading,	With standard wafer scanner for standard silicon wafers
	standard, 4-8" wafers	Bottom side wafer lifting blade with vacuum hold
		• For standard thickness and "low warp" thinned wafers
		• Requires wafer chuck with lift pins
X2-EHS48P	Wafer end effector for auto-loading,	· With advanced wafer scanner for non-silicon, glass and non-standard wafers
	standard, 4-8" wafers	Bottom side wafer lifting blade with vacuum hold
		• For standard thickness and "low warp" thinned wafers
		Requires wafer chuck with lift pins
X2-EVTS48	Wafer end effector for auto-loading,	Top-side wafer lifting blade, patented Vacuum Grip (3-point/center)
	top-side, 4-8" wafers	Optimized for "compliant handling" of warped thinned wafers
		 Supports standard wafers and all chucks (with or without lift pins)
X2-ECTS68	Wafer end effector for auto-loading,	Top-side wafer lifting blade with CYCLONE "Bernoulli" design
	top-side, edge, 6-8" wafers	Edge grip for warped thinned wafers (6 mm exclusion required)
		Supports standard wafers and all chucks (with or without lift pins)
X2-ECTS4	Wafer end effector for auto-loading, top-side, edge, 4" wafers	Top-side wafer lifting blade using CYCLONE "Bernoulli" design
		Edge grip for warped thinned wafers (6 mm exclusion required)
		Supports standard wafers and all chucks (with or without lift pins)

> Velox Probe Station Control Software

The TESLA200 is equipped with Velox probe station control software and optional VeloxPro SEMI E95-compliant test executive software that enables simplified and safe automation of the entire wafer test cycle. Operating system is Windows 10.

Velox Probe Station Control Software

Velox software provides all features and benefits required for semi- and fully-automated operation of the probe system, such as:

- · User-centered design: Minimized training costs and enhanced efficiency.
- Windows 10 compatible: Highest performance and safe operation with state-of-the-art hardware.
- · Loader integration: No need for any additional software. Easy creation of workflows and receipts.
- Smart automation features: Faster time to data due to reduced test cycle times.
- Hundreds of tuneable options: High flexibility for a large variety of applications.
- · Simplified operation for inexperienced users: Reduced training costs with Workflow Guide and condensed graphical user interface.

VeloxPro Package (Optional)

VeloxPro is a SEMI E95-compliant enhancement with test executive capabilities, featuring:

- · SEMI E95-compliant probe station control software with condensed graphical user interface for simplified operation
- · Test executive software enabling control of third-party measurement equipment via the probe station

Tester Interface

The TESLA200 uses commands through GPIB as a permanent listener. The GPIB interface provides the ability to:

- · Request an inventory of all wafers available in the cassettes
- · Define a wafer map
- Define a job (out of wafers and recipe)
- · Change chuck temperature and initiate re-alignment
- · Receive notifications when the wafer is aligned and ready to test

FORMFACTOR™

> Thermal System Performance

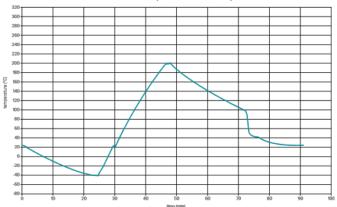
Thermal System Overview			Coax	Standard	High Current
Temperature ranges	-50°C to 200°C, ATT, liquid cool (200 mm)		•	•	•
	-55°C to 300°C, ATT, air cool (200 mm)		•	•	•
	-40°C to 300°C, ATT, air cool (200 mm)		•	•	•
	+20°C to 300°C, ATT, air cool (200 mm)		•	•	•
	+30°C to 300°C, ATT, air cool (200	mm)	•	•	•
Wafer temperature accuracy	Standard ^{1,2}	± 2.5°C at 100°C			
	High Accuracy³	± 0.05°C (0 to 250°C)			
Thermal uniformity	Coax, Standard, High Current ⁴	≤± 0.5C° @ 25°C, ≤±	1.5°C @ -60°C,	≤± 0.85°C @ 200°C	C, ≤ ± 1.5°C @ 300°C

^{1.} As measured with an Anritsu WE-11K-TSI-ANP or WE-12K-GW1-ANP type K thermocouple surface temperature measurement probe with offset calibration procedure. Conditions: closed chamber with minimum recommended purge air, probe centered on a blank silicon wafer, chuck at center of travel and standard probe height. Typical type K thermocouple probe tolerances are ±2.2°C or ±0.75% of the measured temperature in °C (whichever is greater).

ATT Thermal System Specifications, 200 mm (liquid cool, -55°C to 200°C)

Temperature ranges	-55°C to 200°C
Transition time – Heating (-55°C to 25°C)	5 min (typical)
Transition time – Heating (25°C to 200°C)	14 min (typical)
Transition time – Cooling (200°C to 25°C)	34 min (typical)
Transition time – Cooling (25°C to -55°C)	20 min (typical)
Temperature resolution	0.1° C
Audible noise	< 60 dB (A)

ATT Thermal Transition Time (-55°C to 200°C)

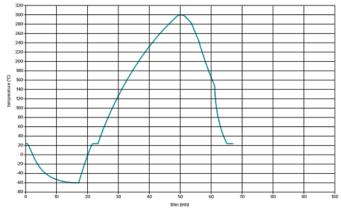


Typical times using TESLA200-AP with FemtoGuard Chuck.

ATT Thermal System Specifications, 200 mm (air cool, -60°C to 300°C)

C to 300°C
n (typical)
nin (typical)
nin (typical)
nin (typical)
dB (A)

ATT Thermal Transition Time (-60°C to 300°C)



Typical times using TESLA200-AP with FemtoGuard Chuck.



^{2.} The test setup can change the wafer temperature accuracy from the calibration by ±5°C (typical). Test setup attributes include open or closed chamber, probe or probe card construction and number of contacts, purge air flow rate, and lab environmental conditions.

^{3.} Special high accuracy calibration using KLA Sense array wafer (Consult factory for pricing and availability)

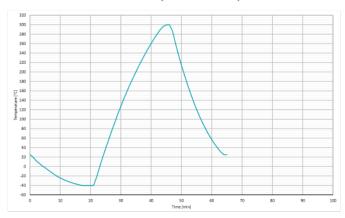
^{4.} As measured at DUT (device under test) probing location.

> Thermal System Performance (continued)

ATT Thermal System Specifications, 200 mm (air cool, -40°C to 300°C)

	Standard Mode	Power Mode
Temperature range	-40°C to 300°C	-40°C to 300°C
Transition time — Heating (-40°C to 25°C)	5 min (typical)	5 min (typical)
Transition time – Heating (25°C to 300°C)	27 min (typical)	27 min (typical)
Transition time — Cooling (300°C to 25°C)	18 min (typical)	14 min (typical)
Transition time — Cooling (25°C to -40°C)	22 min (typical)	19 min (typical)
Temperature resolution	0.1°C	0.1°C
Audible noise	< 55 dB (A)	< 55 dB (A)

ATT Thermal Transition Time (-40°C to 300°C)

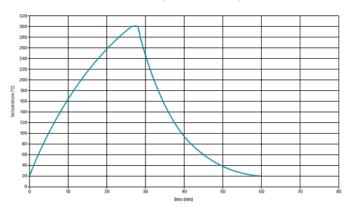


Typical times using TESLA200-AP with FemtoGuard Chuck.

ATT Ambient Option Specifications, 200 mm (air cool, + 20°C to 300°C)

Temperature range	+ 20°C to 300°C
Transition time - Heating	27 min 200 mm (typical)
Transition time - Cooling	31 min 200 mm (typical)
Temperature resolution	0.1°C
Audible noise	< 55 dB (A)

ATT Thermal Transition Time (+20°C to 300°C)

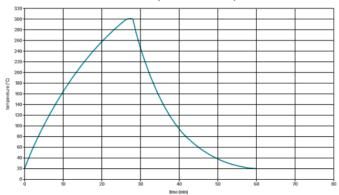


Typical times using TESLA200-AP with FemtoGuard Chuck.

ATT Ambient Option Specifications, 200 mm (air cool, +30°C to 300°C)

Temperature range	+ 30 to 300°C
Transition time - Heating	25 min (typical)
Transition time - Cooling	36 min (typical)
Temperature resolution	0.1°C
Audible noise	< 55 dB (A)

ATT Thermal Transition Time (+30°C to 300°C)



Typical times using TESLA200-AP with FemtoGuard Chuck.



> TESLA200 Station Models and Included Features

Station Type	Fully-au	Fully-automated		Semi-automated	
Models	AP	М	AP	M	
Features					
High-power safety enclosure (TUV certified)	•	•	•	•	
MicroChamber for dark, dry and enhanced EMI-shielding enclosure	•	•	•	•	
PureLine technology for premium signal path fidelity	•		•		
AttoGuard for enhanced IV and CV testing	•		•		
F. II					

Fully-automatic station (base)

- · Precision 4-axis 200 mm wafer stage
- High rigidity universal platen for stable probe contact
- · Station frame with integrated control electronics and computer (with LCD, ergo mounts)
- · Passive vibration isolation for full-auto station frame
- · Automatic wafer loader module (incl. single cassette port, robot, pre-aligner)
- · Velox probe station control software, with
 - + Complete automation tools AutoAlign, AutoDie, AutoXYZT Correction
 - + Thermal control, video window, wafermap, remote access
- · User guides, tools, and accessories, and universal power cord kit

Semi-automatic station (base)

- Precision 4-axis 200 mm wafer stage
- · High rigidity universal platen for stable probe contact
- · Station frame with integrated control electronics and computer (with LCD, ergo mounts)
- · Passive vibration isolation for semi-auto station frame
- · Velox probe station control software, with
 - + Complete automation tools AutoAlign, AutoDie, AutoXYZT Correction
 - + Thermal control, video window, wafermap, remote access
- · User guides, tools, and accessories, and universal power cord kit

Microscope bridge / transport – High stability programmable 50 mm (2x2") (X2-TMT50P)	•		•	
Microscope bridge / transport – High stability manual 50 mm (2x2") (X2-MT50)		•		•
Manual XY ergonomic controls for motorized wafer stage (X2-TXYCTRL)	•		•	
Precision 4-point platen lift and kinematic mount (X2-PLA)	•		•	
Fixed platen mount (X2-FPM)		•		•
High temperature stability module for platen (X2-HTSM)	•		•	
Fixed chuck mount adapter (non-rollout) (X2-FCM)	•	•		
Wafer chuck rollout module (X2-WRO)			•	•
Smart door lock for MicroChamber (X2-DLCK)	•		•	
AUX chucks - High Voltage (positions 1 and 2) (X2-TAUXA1 and X2-TAUXA2)	•		•	
Platen insert - MicroChamber TopHat (8 sides) with AttoGuard (X2-PIMTH8A)	•		•	
Platen insert - MicroChamber TopHat (8 sides) (X2-PIMTH8)		•		•
GPIB Interface (X2-GPIB)	•	•	•	•

 $[\]bullet = \textit{Base features and options included in Model/Package (consult FormFactor representative for more information)}. \\$

> Thermal Options

TESLA200 Non-Thermal Chucks

Chuck Compatibility AΡ **Part Number General Description** TC-007-2x4 Coaxial TESLA Chuck, non-thermal, 200mm (8"), Au

TC-007-2x4-SHV Coaxial TESLA Chuck, non-thermal, 3kV with SHV connectors, 200mm (8"), Au SHV TC-007-4x4 FemtoGuard Triaxial TESLA Chuck, non-thermal, 200mm (8"), Au

TESLA200 Thermal Chucks		Chuck Compatibility	
General Description		AP	M
Coaxial TESLA Chuck, -55°C to +300°C, 200mm (8"), Au	Air		•
FemtoGuard Triaxial TESLA Chuck, standard, -55°C to +300°C, 200mm (8"), Au	Air	•	•
FemtoGuard Triaxial TESLA Chuck, high-current (600A), -55°C to +300°C, 200mm (8"), Au	Air	•	•
Coaxial TESLA Chuck, -50°C to +200°C, 200mm (8"), Au	Liquid		•
FemtoGuard Triaxial TESLA Chuck, standard, -50°C to +200°C, 200mm (8"), Au	Liquid	•	•
FemtoGuard Triaxial TESLA Chuck, high-current (600A), -50°C to +200°C, 200mm (8"), Au	Liquid	•	•
	General Description Coaxial TESLA Chuck, -55°C to +300°C, 200mm (8"), Au FemtoGuard Triaxial TESLA Chuck, standard, -55°C to +300°C, 200mm (8"), Au FemtoGuard Triaxial TESLA Chuck, high-current (600A), -55°C to +300°C, 200mm (8"), Au Coaxial TESLA Chuck, -50°C to +200°C, 200mm (8"), Au FemtoGuard Triaxial TESLA Chuck, standard, -50°C to +200°C, 200mm (8"), Au	General Description Coaxial TESLA Chuck, -55°C to +300°C, 200mm (8"), Au FemtoGuard Triaxial TESLA Chuck, standard, -55°C to +300°C, 200mm (8"), Au Air FemtoGuard Triaxial TESLA Chuck, high-current (600A), -55°C to +300°C, 200mm (8"), Au Air Coaxial TESLA Chuck, -50°C to +200°C, 200mm (8"), Au Liquid FemtoGuard Triaxial TESLA Chuck, standard, -50°C to +200°C, 200mm (8"), Au Liquid	General Description Coaxial TESLA Chuck, -55°C to +300°C, 200mm (8"), Au FemtoGuard Triaxial TESLA Chuck, standard, -55°C to +300°C, 200mm (8"), Au FemtoGuard Triaxial TESLA Chuck, high-current (600A), -55°C to +300°C, 200mm (8"), Au Coaxial TESLA Chuck, -50°C to +200°C, 200mm (8"), Au Liquid FemtoGuard Triaxial TESLA Chuck, standard, -50°C to +200°C, 200mm (8"), Au Liquid

^{*}x=0 standard (10 kV), x=3 lift pin ready (3 kV limit)

TESLA200 Thermal Systems		Cooling	
Part Number	General Description		
TS-417-02T	Thermal system for SUMMIT200/TESLA200, +30°C to 300°C (100-230 VAC 50/60 Hz)	Air	
TS-417-05T	Thermal system for SUMMIT200/TESL200, +20°C to 300°C (100-230 VAC 50/60 Hz)	Air	
TS-427-08R	Thermal system for SUMMIT200, -40°C to 300°C, ATT, air cool (200-220 VAC 60 Hz, UL-certified)	Air	
TS-427-08P	Thermal system for SUMMIT200, -40°C to 300°C, ATT, air cool (200-230 VAC 50/60 Hz)	Air	
TS-417-14R	Thermal system for SUMMIT200/TESL200, -60°C to 300°C (200-220 VAC 60 Hz, 200 VAC 50 Hz)	Air	
TS-417-14E	Thermal system for SUMMIT200/TESL200, -60°C to 300°C (200-240 VAC 50 Hz)	Air	
TS-407-07E	Thermal system for SUMMIT200/TESL200, -55°C to 200°C (230 VAC 50 Hz)	Liquid	

Note: Thermal systems must match the thermal chuck selected, i.e. TS-417-xxx thermal systems are compatible only with TC-417-xxx chucks.

> Standard Options for Microscope Mounts

High Stability Bridge/Transport (programmable)	Part Number X2-TMT50P	
Travel X-Y	50 mm x 50 mm (2 in. x 2 in.)	
Travel X-Y in 8-sided TopHat and shielded probe card adapters	26 mm x 26 mm (1 in. x 1 in.)	
Travel X-Y in 4-sided RF TopHat	5 mm x 5 mm (0.2 in. x 0.2 in.)	
Туре	Stepper motor with closed loop encoder system	
Resolution X-Y	0.4 μm (0.016 mils)	
Repeatability X-Y	≤ 2 µm (0.08 mils)	
Accuracy X-Y	≤ 5 µm (0.2 mils)	
Speed X-Y	5 mm (0.2 in.) /sec	
Planarity	10 μm (0.4 mils) over full travel with 5 kg (11 lb.) load	
Z gross lift	100 mm (4 in.) vertical lift, pneumatic with up/down, for easy probe access	
Z gross repeatability	1 μm (0.04 mils)	
Z focus	Coarse/fine focus uses microscope system	



> Standard Options for Microscope Mounts (continued)

High Stability Bridge/Transport (manual)	Part Number X2-MT50
Travel X-Y	50 mm x 50 mm (2 in. x 2 in.)
Travel X-Y in 8-sided TopHat and shielded probe card adapters	26 mm x 26 mm (1 in. x 1 in.)
Travel X-Y in 4-sided RF TopHat	5 mm x 5 mm (0.2 in. x 0.2 in.)
Resolution X-Y	5 mm (0.2 in.) / turn, coaxial XY control
Planarity	10 μm (0.4 mils) over full travel with 5 kg (11 lb.) load
Z gross lift	4" vertical lift, pneumatic with up/down, for easy probe access
Z gross repeatability	1 μm (0.04 mils)
High Stability Bridge/Transport (manual, fixed XY)	Part Number X2-MTF
Planarity	10 μm (0.4 mils) over full travel with 5 kg (11 lb.) load
Z gross lift	4" vertical lift, pneumatic with up/down, for easy probe access
Z gross repeatability	1 μm (0.04 mils)

> TESLA200 Station Accessories

Microscope / video system	
Probe card holders	
RF and DC probes, needles and probe cards	
RF and DC cables and adapters	
RF and DC probe positioners	
Calibration software and standards	
Vacuum pump, air compressor	

> Probing Kits

Probing kit includes necessary accessories, such as high-current/voltage probes, probe holders, positioners and interconnect cables for typical vertical and lateral device measurement setup.

Probing Kit for Keysight B1505A

Item	Description
High-current probe package	HCP high-current parametric probe holder with BNC connector (quantity of two)
	Replaceable probe tips (box of five)
	Probe micropositioner (quantity of two)
High-voltage probe package with Kelvin sense capability	HVP high-voltage parametric probe holders with SHV connectors (quantity of three), or with Keysight triaxial connectors (quantity of two)
	Replaceable probe tips (box of 25)
	Probe micropositioner (quantity of five)
System interface panels	Keysight B1505A accessory mounting kit
Cables	Basic cable kit for Keysight B1505A accessory connection, including probe-to-panel, panel-to-chuck and chuck-to-instruments cables



> Probing Kits (Continued)

Probing Kit for Keithley Equipment 236/237

Description
HCP high-current parametric probe holder with banana jack (quantity of two)
Replaceable probe tips (box of five)
Probe micropositioner (quantity of two)
HVP high-voltage parametric probe holders with Amphenol triaxial connectors (quantity of three)
Replaceable probe tips (box of 25)
Probe micropositioner (quantity of three)
High-voltage interface panel (triaxial)
High-current interface panel
High-voltage triaxial cable package, including probe-to-panel, panel-to-instrument and chuck-to-instruments cables

> VueTrack™ Technology Upgrade

The VueTrack technology provides a novel method to track probe tips and correct for drift, allowing a customer to run a probe station unattended at multiple temperatures with no operator intervention. The VueTrack technology significantly increases test productivity and test cell efficiency by eliminating the idle time between temperature transitions and automatically generating parametric and reliability data. VueTrack technology works best with high thermal stability probe arms/probe card holder.

Available Items*

Part Number	Description
151-243	VueTrack 30 day demo license**
X2-PIPCHMH	HTS Probe Card Holder, 40 mm, universal
151-359	VueTrack onsite PTPA option**
	Various HTS single probe arms*

^{*} See FormFactor's Station Accessory Guide for other available items, such as HTS probe arms and probe tips.

> Regulatory Compliance

Certification	TÜV compliance tested for CE and CB, certified for US and Canada, SEMI S2 and S8	
---------------	--	--

> Warranty*

Warranty	Fifteen months from date of delivery or twelve months from date of installation
Service contracts	Single and multi-year programs available to suit your needs

^{*}See Terms and Conditions for Sale for more details.

© Copyright 2022 FormFactor, Inc. All rights reserved.
FormFactor and the FormFactor logo are trademarks of FormFactor, Inc. All other trademarks are the property of their respective owners.

Al information is subject to change without notice.

Corporate Headquarters 7005 Southfront Road Livermore, CA 94551 Phone: 925-290-4000 www.formfactor.com

TESLA200-DS-0822



^{**} eVue PRO model required. Contact FormFactor for eVue PRO upgrade.